



Sheet 1 of 1

PTO-1449 (Modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. 213.003-D2-US	SERIAL NUMBER 10/763,142
	APPLICANT(S) Ye et al.	
	FILING DATE January 22, 2004	GROUP ART UNIT 2425 2857

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<i>ER</i>	5,907,820	5/1999	Pan			
	5,967,661	10/1999	Renken et al.			
	6,033,922	3/2000	Rowland et al.			
	6,051,443	4/2000	Ghio et al.			
	6,244,121	6/2001	Hunter			
	6,630,995	10/2003	Hunter			
	6,693,708	2/2004	Hunter			
	6,707,545	3/2004	Hunter			
	6,721,045	4/2004	Hunter			

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<i>QR</i>	4,585,342	4/1986	Lin et al.			
	4,701,606	10/1987	Tanimoto et al.			
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	5,202,748	4/1993	MacDonald et al.			
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	5,969,639	10/1999	Lauf et al.			
	5,978,085	11/1999	Smith et al.			
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gk	6,356,345	3/2002	McArthur et al.			
	2001/0055415	12/2001	Nozaki			
	2002/0003216	1/2002	Kida et al.			
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	2002/0036775	3/2002	Wolleschensky et al.			
	2002/0041377	4/2002	Hagiwara et al.			
	2002/0062206	5/2002	Liebchen			
	2002/0067478	6/2002	Karpol et al.			
	2002/0070355	6/2002	Ota			
	5,597,868	1/1997	Kunz			
	5,914,774	6/1999	Ota			
	5,891,959	4/1999	Kunz			
	5,973,316	10/1999	Ebbesen et al.			
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<i>AW</i>	6,040,936	3/2000	Kim et al.			
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	6,236,033	5/2001	Ebbesen et al.			
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	6,278,101	8/2001	Puyot			
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	6,368,763	4/2002	Drksen et al.			
	6,515,272	2/2003	Fontaine et al.			
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<i>ML</i>	2002/0167651	11/2002	Boonman et al.			
	2002/0172876	11/2002	Baselmans			
	2003/0001107	1/2003	Kroon et al.			
	2003/0017805	1/2003	Yeung et al.			
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<i>ENC</i>	6,451,490	9/2002	Advocate et al.			
	6,534,798	3/2003	Scherer et al.			
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EW	EP 0 628 806	4/1994	European			
J	WO 00/59206	10/2000	PCT			
J	WO 02/17030	2/2002	PCT			

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EW	"A New Mask Evaluation Tool, the Microlithography Simulation Microscope Aerial Image Measurement System", Budd, et al., SPIE Vol. 2197, 1994, pp.530-540
J	"Characterization of Lithographic System Performance Through Direct Aerial Image Measurements", C.H. Fields, SRC/SEMATECH, 1996 (96-MC-500)
J	"Aerial Image Measurements on a Commercial Stepper", Fields, et al., SPIE Vol. 2197, 1994, pp.585-595
J	"A Novel High-Resolution Large-Field Scan-and-Repeat Projection Lithography System", K. Jain, SPIE Vol. 1463 Optical/Laser Microlithography IV, 1991, pp.666-677
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J	"Improving Photomask Linewidth Measurement Accuracy via Emulated Stepper Aerial Image Measurement", J. Potzick, SPIE Vol. 2322, Photomask Technology and Management, 1994, pp.353-359
J	"Pattern Shape Analysis Tool for Quantitative Estimate of Photomask and Process", Yonekura, et al., Proceedings of SPIE Vol. 4409, Photomask and Next-Generation Lithography Mask Technology VIII, 2001, pp.204-211
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<i>ant</i>	"Application of the Aerial Image Measurement System (AIMS™) to the Analysis of Binary Mask Imaging and Resolution Enhancement Techniques", Martino et al., SPIE Vol. 2197, 1994, pp.573-584
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<i>V</i>	"Near-Field Optics: Microscopy, Spectroscopy, and Surface Modification Beyond the Diffraction Limit", Betzig and Trautman, Science, Vol. 257, July 1992, pp.189-195

EXAMINER <i>Richard Reynold</i>	DATE CONSIDERED <i>8/18/04</i>
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<i>✓</i>	"Wafer-Mounted Sensor Arrays for Plasma Etch Processes", M. Freed, Ph.D. Dissertation, University of California, Berkeley, Fall 2001

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	6,642,063	11/2003	Mundt et al.			
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